Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	7066	((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/23 22:00
S2	486	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:46
S3	594	(soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:46
S4	16042	locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:37
S5	2	(((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))) and (((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/434) or (438/449) or (438/447) or (438/449) or (438/447) or (438/449) or (438/450) or (438/547) or (438/546) or (438/547) or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:24
		(438/561) or (438/766) or (438/769) or (438/770)).CCLS.)				

				1	γ	
S6	6	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:24
S 7	14	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:25
S8	6	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)) same (trench\$2 or groove\$1 or open\$3 or hole)) and (((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)). CCLS.)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:28
S9	47	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)) same (trench\$2 or groove\$1 or open\$3 or hole)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:29
S10	5	("4292091" "4319954" "4323417" "4338139" "4339285").PN.	USPAT	OR	OFF	2004/08/12 14:31
S11	20	"4437225".URPN.	USPAT	OR	OFF	2004/08/12 14:32
S12	16	("4437225" "4683637" "4700454" "4810664" "5032535" "5114872" "5279978" "5418174" "5460983" "5482872" "5527719" "5610088" "5612239" "5612249" "5712173" "5733813").PN.	USPAT	OR	OFF	2004/08/12 14:35
S13	11	("4437225" "4863878" "4948742" "5182226" "5346841" "5441094" "5472902" "5488004" "5494846" "5707899" "5712186").PN.	USPAT	OR	OFF	2004/08/12 14:37
S14	107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:49

				,		
S15	11	(((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/524) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.) and ((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:41
S16	62	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2004/08/12 14:54
S17	51	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))) not ((((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/449) or (438/445) or (438/447) or (438/449) or (438/450) or (438/52) or (438/524) or (438/561) or (438/766) or (438/769) or (438/770)). CCLS.) and ((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:44
S18	5	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:53

S19	12	((implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same oxidiz\$5) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:56
S20	59	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same oxidiz\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 14:56
S21	486	implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:26
S22	594	(soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:27
S23	107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 21:17
S24	0	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) same ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:58
S25	14	(implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film))) and ((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:28
S26	6	("5955767" "6100159" "6174754" "6403433" "6501133" "6515333"). PN.	USPAT	OR	OFF	2004/08/12 16:32
S27	0	"6724049".URPN.	USPAT	OR	OFF	2004/08/12 16:33
S28	1	"6501133".URPN.	USPAT	OR	OFF	2004/08/12 16:34
S29	8	("5614729" "5920097" "5955767" "6100159" "6130457" "6174754" "6287901" "6303412").PN.	USPAT	OR	OFF	2004/08/12 16:34

S30	41	((soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)) same (fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:58
S31	107731	fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 21:18
S32	92	(fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)) near10 (sidewall\$1 near trench\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 21:45
S33	18	(fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)) near10 ((etch\$3 near5 sidewall\$1) near3 trench\$2)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 21:46
S34	995	oxide near2 (layer or film) same ((ion near2 implant\$4) near5 (oxygen near ion))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 15:37
S35	16042	locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:37
S36	15	(oxide near2 (layer or film) same ((ion near2 implant\$4) near5 (oxygen near ion))) same (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:37
S37	325	oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 15:36
S38	49	(locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:44

S39	8	(locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:44
S40	41	((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 15:33
S41	276	(oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:52
S42	0	((oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))) and (locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 12:52
S43	41	((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) and (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion)))) not ((locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)) same (oxide near2 (layer or film) near5 ((ion near2 implant\$4) near5 (oxygen near ion))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 15:34

S44	74	oxide near2 (layer or film)) same (((ion near2 implant\$4) near5 (oxygen near ion)) same (through near5 (oxide near2 (layer or film)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/13 15:40
S45	2	("5372950" "5972777").PN.	USPAT	OR	OFF	2004/08/16 10:57
S46	2345371	v	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/08/12 16:26
S47	7514	((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/13 14:45
S48	23	S47 and (soi or (silicon near2 insulator)) near5 (fully near2 deplet\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:55
S49	4	S48 and (implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 21:58
S50	19	S48 not S49	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:47
S51	84	S47 and (implant\$4 near5 (oxygen near2 ion\$1) near10 (silicon near2 (layer or film)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:49
S52	31	S51 and (fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:53

S53	331	(fox or locos or (f adj locos) or (local adj oxidation adj of adj silicon) or (framed adj local adj oxidation adj of adj silicon)or (field near2 oxide)) near (silicon near (layer\$1 or film\$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:54
S54	58	S53 and (soi or (silicon near2 insulator))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/13 14:55
S55	6	("5863823" "5946595" "5965917" "5994191" "6015752" "6165903"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/05/13 14:57
S56	48	("3562425" "3699544" "3829743" "3829881" "4037140" "4065781" "4177084" "4183134" "4198649" "4282556" "4385937" "4418470" "4420743" "4425700" "4463492" "4509990" "4523963" "4549198" "4588447" "4598305" "4607176" "4615762" "4617066" "4659392" "4717836" "4766482" "4775641" "4843442" "4843448" "4851721" "4872010" "4876582" "4907041" "4989057" "5027171" "5141882" "5166767" "5170373" "5196802" "5229644" "5242849" "5294823" "5300443" "5313077" "5341009" "5391903" "5416043" "5445802"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/05/13 14:58
S57	3	("20010005030" "5279978" "5463238").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/05/13 15:05
S58	6	("5145802" "5151381" "5334550" "5358890" "5374586" "5422287"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/05/13 15:09
S59	8	("3690968" "3974515" "4729006" "4983535" "5060035" "5340999" "5381029").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/05/13 15:12
S60	951	((implant\$4 or dop\$3) near5 (oxygen near2 ion\$1)) near10 (oxide or (pad near2 oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:07

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S61	7596	((438/42) or (438/225) or (438/297) or (438/298) or (438/362) or (438/423) or (438/426) or (438/433) or (438/434) or (438/439) or (438/440) or (438/444) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/546) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/31 13:59
S62	104	S60 and S61	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:02
S63	97	S62 and ((oxid\$5 or fox or (field near3 oxid\$5) or locos or (local near3 oxid\$5)) same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:24
S64	5	("4683637" "5712173" "5976952" "6069054" "6258693").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/08/23 22:14
S65	3	("5393693" "5445989" "5498566"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/08/23 22:18
S66	762	S60 and ((oxid\$5 or fox or (field near3 oxid\$5) or locos or (local near3 oxid\$5)) same silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:08
S67	665	S66 not S62	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:24
S68	570	S67 and (semiconductor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:26
S69	306	S68 and (nitride)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:26

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S70	222	S69 and (isolat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/23 22:26
S71	1	("20050077580").PN.	US-PGPUB; USPAT	OR	OFF	2005/09/13 19:54
S72	1	("6489650").PN.	US-PGPUB; USPAT	OR	OFF	2005/09/13 19:54
S73	3	("5616942" "5831299" "5841185"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/13 19:55
S74	3314	(implant\$3 or inject\$3) near5 oxygen near5 (silicon or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:08
S75	77832	("438"/\$.ccls. or "257"/\$.ccls.) and ((implant\$3 or inject\$3) near "5" oxygen naer5 through near5 (oxide or (pad adj oxide)) or (thermal adj oxide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 15:17
S76	2120	S74 and S75	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 15:17
S77	11475	("438"/\$.ccls. or "257"/\$.ccls.) and ((implant\$3 or inject\$3) near5 oxygen near5 through near5 (oxide or (pad adj oxide)) or (thermal adj oxide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 15:18
S78	368	S77 and S74	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 15:18
S79	61	S78 and (pad adj oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/14 15:18

S80	2	("4523213" "5712186").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/14 15:43
S81	7	("5173444" "5229318" "5308787" "5399520" "5468657" "5470783" "5472906").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/14 15:44
S82	4	("4889829" "4929565" "5476809" "5547886").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/14 15:46
S83	6	("4437225" "4676841" "4725561" "4810664" "4835113" "4921812"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/09/14 15:52
S84	18	("5346841").URPN.	USPAT	OR	OFF	2005/09/14 15:53
S85	10506	((438/42) or (438/221) or (438/225) or (438/296) or (438/297) or (438/298) or (438/359) or (438/362) or (438/400) or (438/423) or (438/424) or (438/425) or (438/433) or (438/434) or (438/439) or (438/440) or (438/445) or (438/447) or (438/449) or (438/450) or (438/452) or (438/547) or (438/547) or (438/561) or (438/766) or (438/769) or (438/770)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/31 14:06
S86	116	S85 and ((implant\$4 or dop\$3) near5 (oxygen near2 ion\$1)) near10 (oxide or (pad near2 oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:07
S87	349	S85 and (implant\$3 or inject\$3) near5 oxygen near5 (silicon or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:08
S88	324	S87 and (oxid\$5 or fox or (field near3 oxid\$5) or locos or (local near3 oxid\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/31 14:10
S89	1009683	"O.sub.2" or oxygen	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:15

S90	616603	implant\$6 or dop\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:16
S91	25393	concentration\$1 with peak	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:18
S92	25395	concentration\$1 with peak\$1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:18
S93	3219803	"Si" or silicon or "SOI" or silicon\$1on\$1insulat\$3 or (silicon adj on adj insulat\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:19
S94	170	S89 same S90 same S92 same S93	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/06/11 14:19

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